## Photochemical Generation of an Intermediate Containing a Silicon-Carbon Double Bond or Its Equivalent from 1,1-Diphenylsilacylobutane

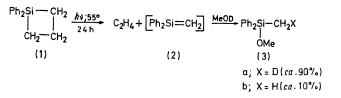
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Summary Photolysis of 1,1-diphenylsilacyclobutane at 2537 Å and 55° produces a high yield of the novel intermediate  $Ph_2Si=CH_2$  which adds MeOD.

ALTHOUGH silacyclobutanes have been studied extensively,<sup>1</sup> their photochemistry has been overlooked. We have found that irradiation of 1,1-diphenylsilacyclobutane (1) at 2537 Å produces the unstable intermediate  $Ph_2Si=CH_2$  (2) in very high yield.<sup>2</sup> Intermediate (2) could be trapped as  $Ph_2(CH_2D)SiOMe$  (3a) by carrying out the photolysis in cyclohexane-methan[<sup>2</sup>H]ol solution.

The reaction is 80% complete after 24 h and (3) was obtained (ca. 95% yield) in high isotopic purity (ca. 90%).



It was isolated by preparative g.l.c. and identified by comparison with a known sample of  $Ph_2(Me)SiOMe$ . The presence of deuterium in (3a) was shown by an exact mass measurement on the parent peak (Found: m/e 229·1024) and the isotopic purity was estimated by measuring the relative

(1) + MeOD 
$$\frac{Cyclohexane}{reflux; 24h}$$
 Ph<sub>2</sub>Si-CH<sub>2</sub>·CH<sub>2</sub>·CH<sub>2</sub>·CH<sub>2</sub>X  
 $\downarrow$   
OMe  
(4)  
a; X = D (ca.90%)  
b: X = H (ca.10%)

areas of the OMe (s,  $\tau$  6.51, 3.0 H) and Si-CH<sub>2</sub> (m,  $\tau$  9.5, 2.1 H) peaks in the <sup>1</sup>H n.m.r. spectrum.

That generation of (2) from (1) is photo-induced is shown by the different 'dark' reaction in which methan<sup>[2</sup>H]ol opens the silacyclobutane ring to give (4) in a silicon-carbon cleavage reaction expected for an angle-strained Si atom in a small ring.<sup>1</sup> No trace of (3) was detected by g.l.c.

The structure of (4) was deduced from its <sup>1</sup>H n.m.r.

spectrum { $\tau$  2.5 (10H, m, Si-Ph), 6.52 (3H, s, Me), and 8.3—9.3 (6.3H, m,  $[CH_2]_3$ ), and its parent peak (m/e 257). The isotopic purity of (4) was measured from the relative peak heights.

We recently reported<sup>3</sup> that pentaphenylmethyldisilane undergoes photochemical dehydrosilylation to give (2), triphenylsilane, and some minor products. The reaction described here, however, not only gives higher yields of (2) but also is essentially free of side products since ethylene is evolved as a gas. Photolysis of (1) is the most convenient low temperature method of generating intermediates like (2) yet to be reported.<sup>4</sup> We are currently investigating other silacyclobutanes as sources for different Si = C species as part of our study of the properties of these unusual intermediates.5

We thank the National Science Foundation for support and Mr. Kei Miyano for recording the mass spectra.

## (Received, 8th November 1972; Com. 1877.)

<sup>1</sup> For a recent review of the chemistry of silacyclobutanes see R. Damrauer, Organometallic Chem. Rev. (A), 1972, 8, 67.

<sup>2</sup> It has been observed that 1,1-dimethylsilacyclobutane yields Me<sub>2</sub>Si=CH<sub>2</sub> when heated to 550° in the vapour phase: M. C. Flowers and L. E. Gusel'nikov, J. Chem. Soc. (B), 1968, 419. These authors have also reported a vapour-phase addition of water to Me<sub>2</sub>Si=CH<sub>2</sub> to give MesSiOH.

P. Boudjouk, J. R. Roberts, C. M. Golino, and L. H. Sommer, J. Amer. Chem. Soc., 1972, 94, 7926.

<sup>4</sup> For a recent report that the photolysis of a sila-alkene precursor (neat) at 77 or 28 K affords some Me<sub>2</sub>Si=CH<sub>2</sub>, and for the finding

that only traces of 1,1,3,3-tetramethyldislacyclobutane derived from  $Me_2Si=CH_2$  were formed by solution photochemistry (cyclo-hexane; 2537 Å), see T. J. Barton and E. Kline, J. Organometallic Chem., 1972, 42, C21. <sup>6</sup> It has been observed that  $Me_2Si=CH_2$  reacts with heptanal to give oct-1-ene and the cyclic trimer ( $Me_2SiO$ )<sub>8</sub>. This reaction apparently goes through an intermediate containing a silicon-oxygen double bond. D. Roark and L. H. Sommer, submitted for arbitration publication.